

ABSTRACT OF THE DISCLOSURE

A thin-film deposition device for forming an organic thin-film having uniform thickness on a substrate includes a vacuum chamber, a substrate holder provided in the vacuum chamber, and at least one tubular gas supply end that supplies gas towards a substrate mounting-face on the substrate holder. The gas supply end includes therein barriers that control the gas flow in the gas supply end and that are disposed at predetermined intervals toward a gas supply port of the gas supply end. Each of the barriers is provided with a plurality of apertures.